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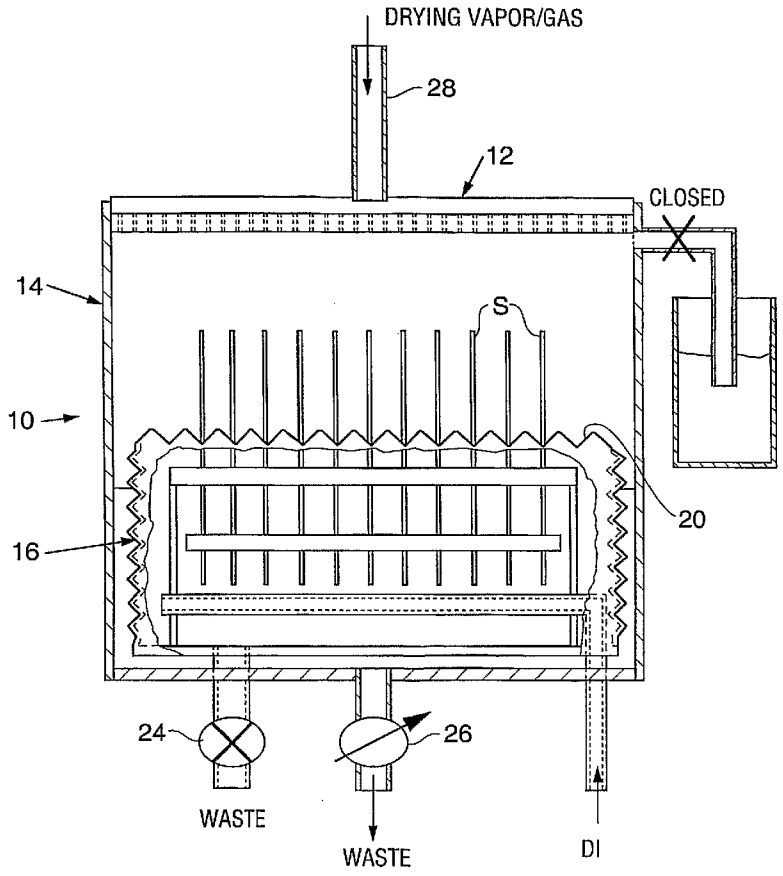
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(54) Title: APPARATUS AND METHOD FOR DRYING SUBSTRATES



(57) Abstract: The present application describes a system for drying substrates which includes a chamber and an inner vessel having an upper edge positioned within the chamber. Process fluid is directed into the inner vessel and allowed to cascade over the upper edge. The upper edge of the inner vessel is lowered to thereby lower the cascade level across the surface of the substrate, while a drying vapor is introduced into the chamber. As the cascade level descends across the surface of the substrate, the substrate surface is exposed to the drying vapor. Megasonic energy may be directed into the inner vessel to accelerate drying using boundary layer thinning.

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